



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

AF/2812  
10/Response  
17/63/01  
A. Walker  
RECEIVED  
JUL 23 2001  
TECHNICAL CENTER 2000

Applicant: Chandra V. Mouli

§ Group Art Unit:

2812

Serial No.: 09/379,092

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Filed: August 23, 1999

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Examiner:

R. Pompey

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For: FORMING SIDEWALL OXIDE  
LAYERS FOR TRENCH  
ISOLATION

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Atty. Dkt. No.: MICT-0042-US

Box AF

Commissioner for Patents

Washington DC 20231

REPLY TO FINAL REJECTION

Sir:

In response to the office action mailed June 28, 2001,  
please consider the following remarks.

Remarks

Claims 1 and 33 stand rejected under §102 based on the  
reference to Hong. (The taking of official notice was only with  
respect to the §103 rejection of the dependent claims.)

Reconsideration of the §102 rejection of claims 1 and 33 is  
requested. Claim 1 calls for implanting impurities which  
enhance the oxidation of said structure beyond that which would  
be expected from crystallographic damage effects. The final  
rejection states that "Hong is silent on what produces the  
oxidation enhancement by implanting dopant species into the  
substrate. Therefore, it is not disclosed whether it is  
crystallographic damage . . ." In view of this statement, it is  
clear that the §102 rejection of claim 1 is not appropriate.

Date of Deposit: 7/16/01  
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Lisa O'Sullivan